



Asok K. Sarka

Group Art Unit: 2829

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Akira SHIMOKOHBE et al.

Application No.: 09/556,795 Examiner:

Filed: April 25, 2000 Docket No.: 106096

For: A THIN FILM-STRUCTURE AND A METHOD FOR PRODUCING THE SAME

AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office Washington, D.C. 20231

Sir:

In reply to the Office Action mailed March 22, 2002, please amend the aboveidentified application as follows:

IN THE CLAIMS:

Please replace claim 3 as follows:

3. (Three Times Amended) A method for producing a thin film-structure comprising the steps of:

forming on a substrate a thin film made of an amorphous material film exhibiting a viscous flow within a range of 10^8 - 10^{13} Pa·S when heated at a temperature within a supercooled liquid phase region;

heating the thin film to a temperature within the supercooled liquid phase region;

deforming the thin film to a given shape without the use of an external force;

and